WE CLAIM:

1. A glass article which includes a glass substrate having thereon a sputter-coated layer system comprising from the glass substrate outward, (a) a substantially metallic layer which includes nickel or a nickel alloy; and (b) an overcoat layer of silicon nitride (Si_3N_4); and wherein the layers are each of sufficient thickness such that when the glass substrate has a thickness of about 1.5 mm-13 mm and has the aforesaid layer system thereon the so-layered glass article is heat treatable, and has a visible transmittance of about 1-80% and a normal emissivity (E_n) of about 0.10-0.60.

2. A glass article according to claim 1 wherein said layer system does not contain any layer of silver; wherein layer (a) is substantially free of any nitride; and wherein said so-layered glass article is durable and chemically resistant.

3. A glass article according to claim 2 wherein said layer system includes an undercoat layer of silicon nitride (Si_3N_4) located between said substantially metallic layer and said glass substrate.

4. A glass article according to claim 2 wherein said substantially metallic layer includes a minor amount of a metallic oxide of the metal in said metallic layer.

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5. A glass article according to claim 4 wherein said layer system includes an undercoat layer of silicon nitride (Si_3N_4) located between said substantially metallic layer and said glass substrate.

6. A glass article according to claim 5 wherein said layer system further includes a substantially stoichiometric metallic oxide layer overcoating, said substantially metallic layer and another substantially stoichiometric metallic oxide layer undercoating said substantially metallic layer.

7. A glass article according to claim 6 wherein said undercoat and overcoat layers of substantially stoichiometric metallic oxide are each contiguous with said substantially metallic layer.

8. A glass article according to claim 1 wherein said layer system comprises a plurality of alternating said substantially metallic layers and said silicon nitride (Si_3N_4) layer is an undercoat layer located between said glass substrate and the first of said plurality of substantially metallic layers.

9. A glass article according to claim 8 wherein said layer system does not contain any layer of silver; wherein

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layer (a) is substantially free of any nitride; and wherein said so-layered glass article is durable and chemically resistant.

10. A glass article according to claim 9 wherein at least one of said substantially metallic layers includes a minor amount of a metallic oxide of the metal in said metallic layer.

11. A glass article according to claim 8 wherein the metal in each of said substantially metallic layers is the same nickel alloy and wherein said silicon nitride layers include a minor amount of a conductive metal.

12. A glass article which includes a glass substrate having thereon a sputter-coated layer system comprising from the glass substrate outward, (a) a layer comprised of a mixture of silicon nitride (Si_3N_4) and nickel or a nickel alloy; and (b) an overcoat layer consisting essentially of silicon nitride (Si_3N_4) and wherein the layers are each of sufficient thickness such that when the glass substrate has a thickness of about 1.5 mm-13 mm and has the aforesaid layer system thereon the so-layered glass article is heat treatable, durable, chemically resistant, and has a visible transmittance of about 1-80% and a normal emissivity (E_n) of about 0.10-0.60.

13. A glass article according to claim 12 wherein said layer system further includes an undercoat layer consisting essentially of silicon nitride (Si_3N_4) located between the glass substrate and said layer (a) and wherein said silicon nitride layers include a minor amount of a conductive metal selected from the group consisting of titanium, zirconium, chromium, hafnium, and mixtures thereof.

14. A method of heat treating a coated glass article comprising the steps of:

(a) sputter-coating onto a glass substrate a layer system comprising from the glass substrate outwardly, a substantially metallic layer which includes nickel or a nickel alloy; and an overcoat layer of silicon nitride; and

(b) thereafter subjecting this coated glass substrate to a heat treatment selected from the group consisting of bending, tempering, heat strengthening and combinations thereof; and

(c) wherein after this heat treatment the resultant article has a normal emissivity (E_n) of about 0.10-0.60 and a visible transmittance of about 1-80%, and wherein said visible and solar transmittance are changed less than about 20% by said heat treatment.

15. The method according to claim 14 wherein said visible and solar transmittance was changed less than about

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10% by said heat treatment; wherein said layer (a) is substantially free of any nitride; and wherein said coated glass article both before and after said heat treatment is durable and chemically resistant.

16. The method according to claim 15 wherein said visible and solar transmittance was changed less than about 2% by said heat treatment.

17. The method according to claim 14 wherein said sheet resistance (R_S) was not increased more than about 10% by said heat treatment.

18. The method according to claim 17 wherein said sheet resistance (R_S) was not increased by said heat treatment.

19. The method according to claim 18 wherein said sheet resistance (R_S) was decreased by said heat treatment.

20. The method according to claim 14 wherein said layer system does not contain any layer of silver, wherein said layer (a) is substantially free of any nitride; and wherein said coated glass article both before and after said heat treatment is durable and chemically resistant.

21. The method according to claim 20 wherein said steps further include sputter coating onto said substrate an undercoat layer of silicon nitride (Si_3N_4) located between said substantially metallic layer and said glass substrate.

22. The method according to claim 20 wherein said substantially metallic layer includes a minor amount of a metallic oxide of the metal in said metallic layer.

23. The method according to claim 22 wherein said steps further include sputter coating onto said substrate an undercoat layer of silicon nitride located between said substantially metallic layer and said glass substrate.

24. The method according to claim 23 wherein said steps further include sputtering a substantially stoichiometric metallic oxide layer overcoat above said substantially metallic layer and sputter coating another substantially stoichiometric metallic oxide layer undercoat beneath said substantially metallic layer.

25. The method according to claim 24 wherein said sputter coating of said undercoat and overcoat layers of substantially stoichiometric metallic oxide occurs immediately before and immediately after, respectively, said sputter coating of said substantially metallic layer so as to be contiguous therewith.

26. The method according to claim 14 wherein said heat treatment is conducted at a temperature from about 1150°F - 1450°F.

27. The method according to claim 14 wherein said silicon nitride layer includes a minor amount of a conductive metal.

28. A method of heat treating a coated glass article comprising the steps of:

(a) sputter coating onto a glass substrate a layer system comprising from the glass substrate outwardly, a layer comprised of a mixture of silicon nitride (Si_3N_4) and nickel or a nickel alloy and thereafter an overcoat layer consisting essentially of silicon nitride; and

(b) thereafter subjecting the coated glass substrate to a heat treatment selected from the group consisting of bending, tempering, heat strengthening and combinations thereof; and

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(c) wherein after this heat treatment the resultant article has a normal emissivity (E_n) of about 0.10-0.60 and a visible transmittance of about 1-80%, and wherein said visible and solar transmittance are changed less than about 20% by said heat treatment.

29. A method according to claim 28 which includes the further step of sputter coating an undercoat layer of silicon nitride (Si_3N_4) so as to be located between said glass substrate and said layer of a mixture of silicon nitride (Si_3N_4) and nickel or nickel alloy.

30. A method according to claim 29 wherein said silicon nitride includes a minor amount of a conductive metal.

31. A method according to claim 28 wherein said heat treatment is conducted at about 1150°F - 1450°F.